US00D702655S

(12) United States Design Patent
Kimura

(10) Patent No.: US D702,655 S
(45) Date of Patent: ** Apr. 15, 2014

(54) **WAFER HOLDER FOR ION IMPLANTATION**

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(**) Term: **14 Years**

(21) Appl. No.: **29/448,067**

(22) Filed: **Mar. 8, 2013**

(30) **Foreign Application Priority Data**

Oct. 15, 2012 (JP) 2012-024964

(51) **LOC (10) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/182**

(58) **Field of Classification Search**
USPC D13/182; 118/500, 728, 729; 414/217, 414/222.01, 416.03, 935, 936, 937, 938, 414/939, 940, 941; 156/345.1, 345.52, 156/345.53
See application file for complete search history.

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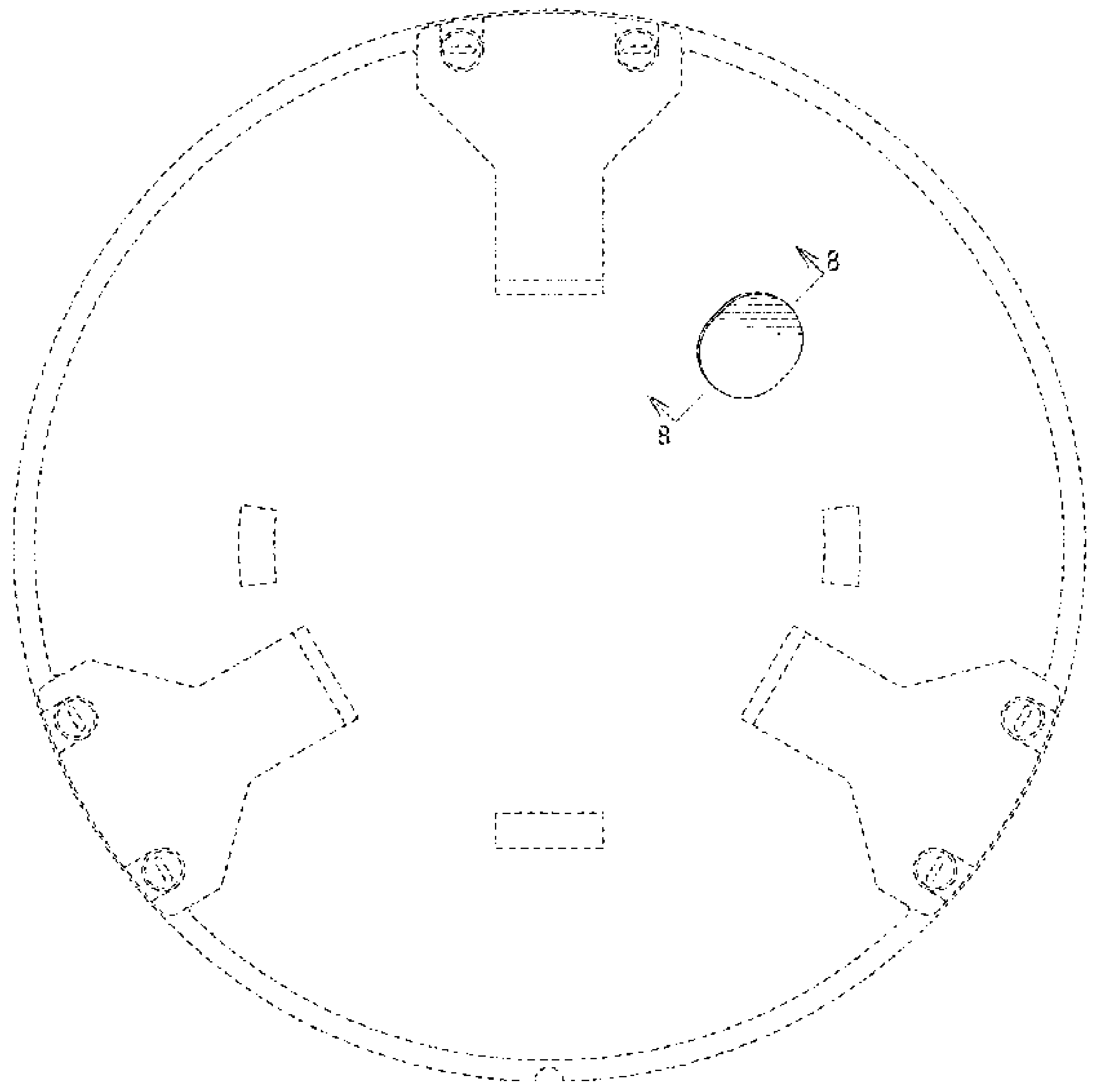
(57) **CLAIM**

The ornamental design for a wafer holder for ion implantation, as shown and described.

DESCRIPTION

FIG. **1** is a front view of a wafer holder for ion implantation showing my new design;
FIG. **2** is a rear view thereof;
FIG. **3** is a top plan view thereof;
FIG. **4** is a bottom plan view thereof;
FIG. **5** is a right side view thereof;
FIG. **6** is a left side view thereof;
FIG. **7** is a perspective view thereof; and,
FIG. **8** is an enlarged cross sectional view taken along line **8-8** of FIG. **3** thereof.
The broken lines shown in the drawings represent portions of the wafer holder for ion implantation that form no part of the claimed design.

1 Claim, 8 Drawing Sheets



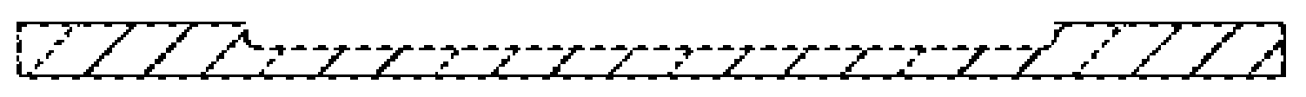


FIG.1

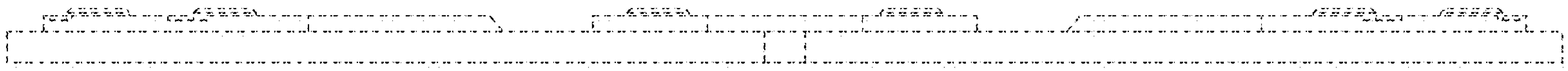


FIG.2

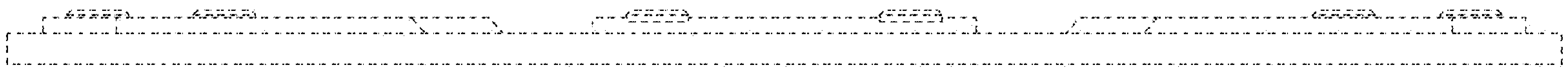


FIG.3

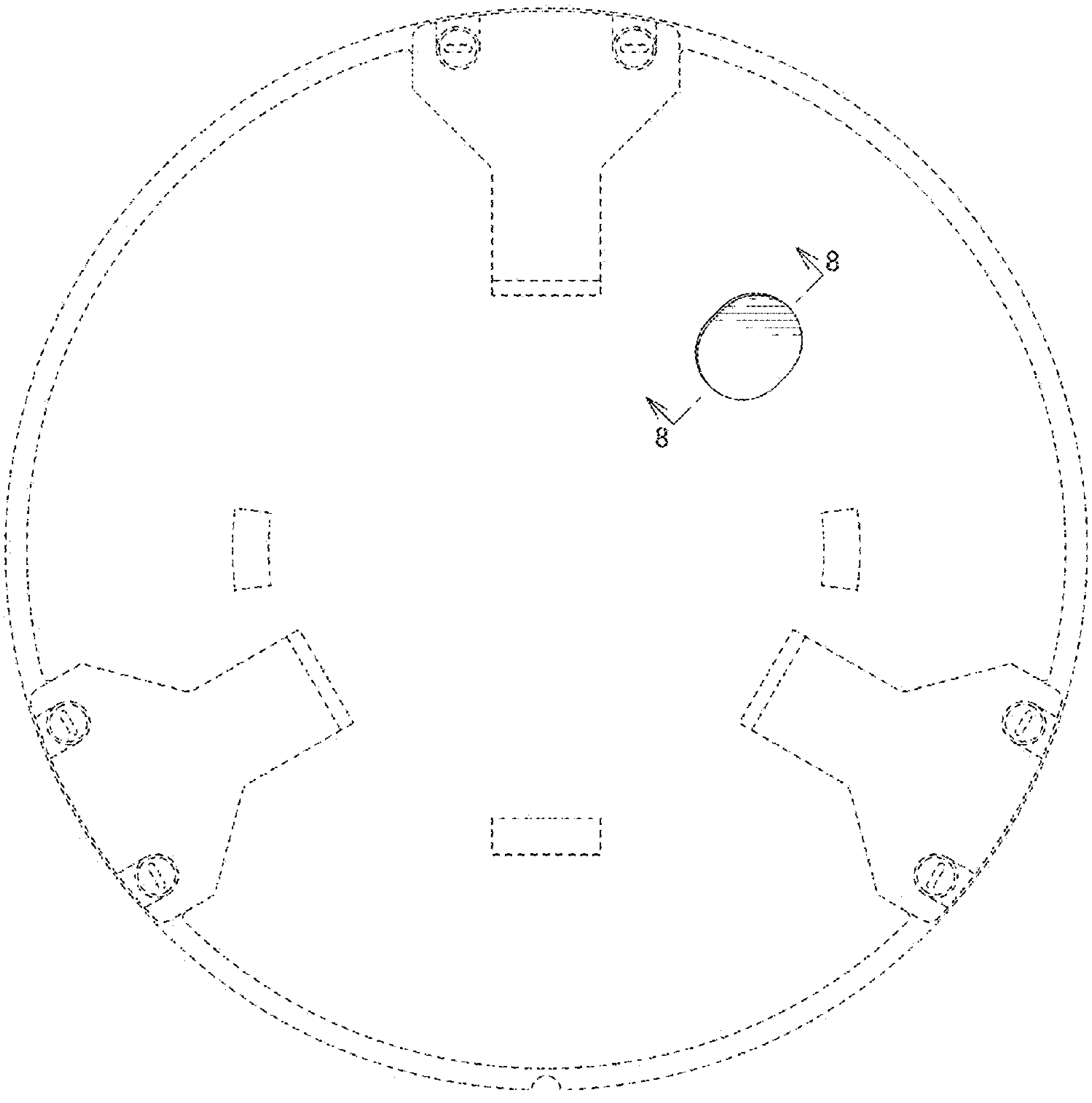


FIG.4

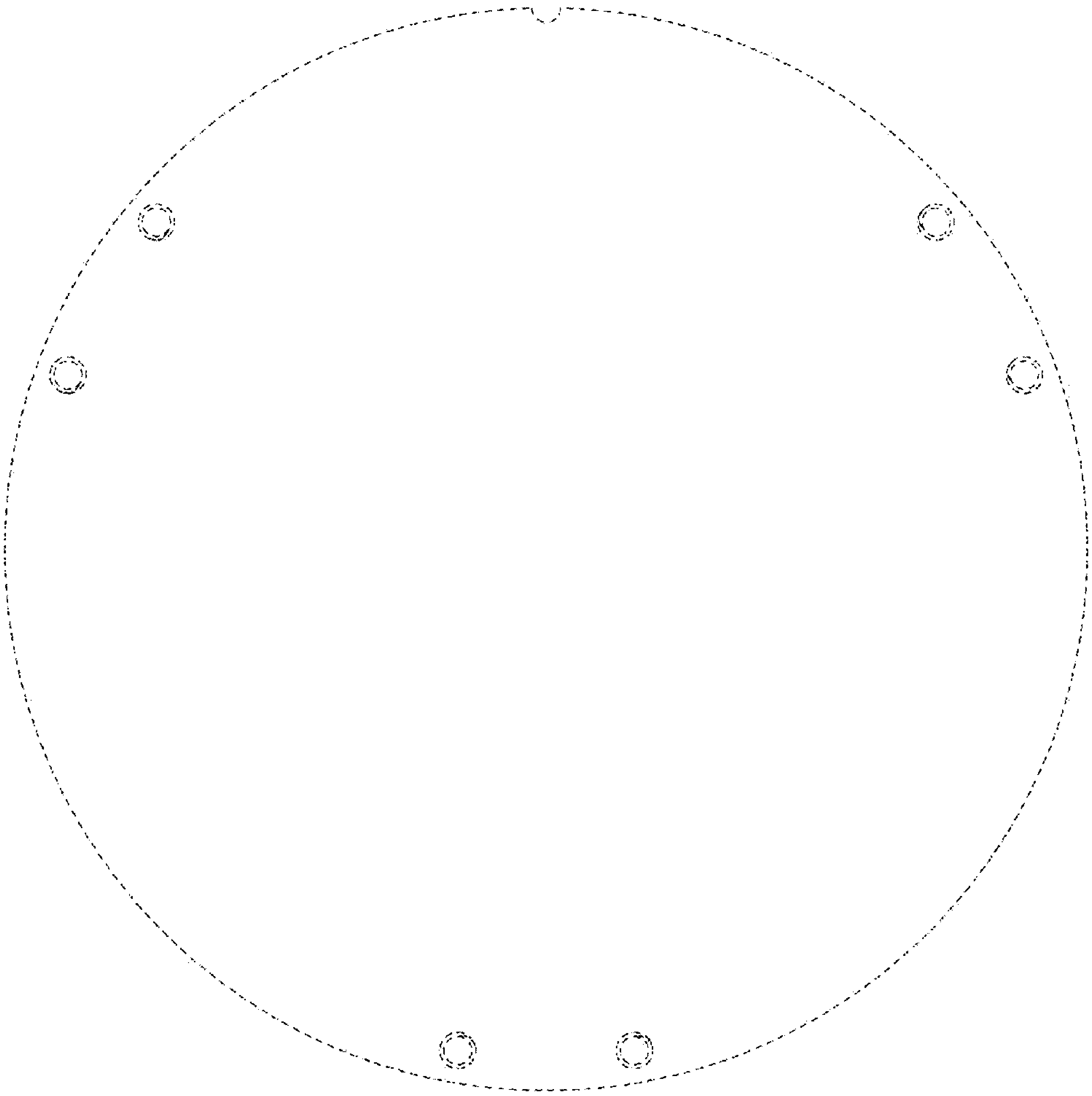


FIG.5

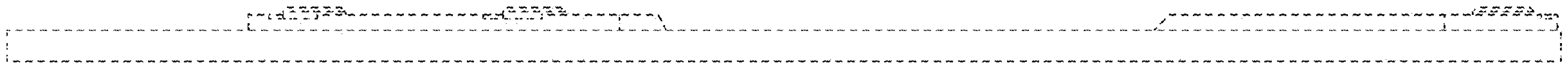


FIG.6

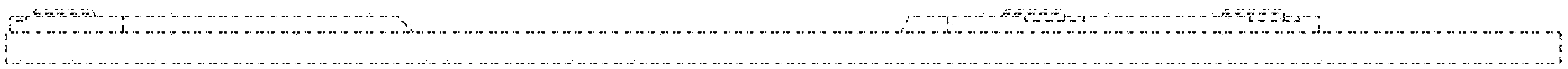


FIG. 7

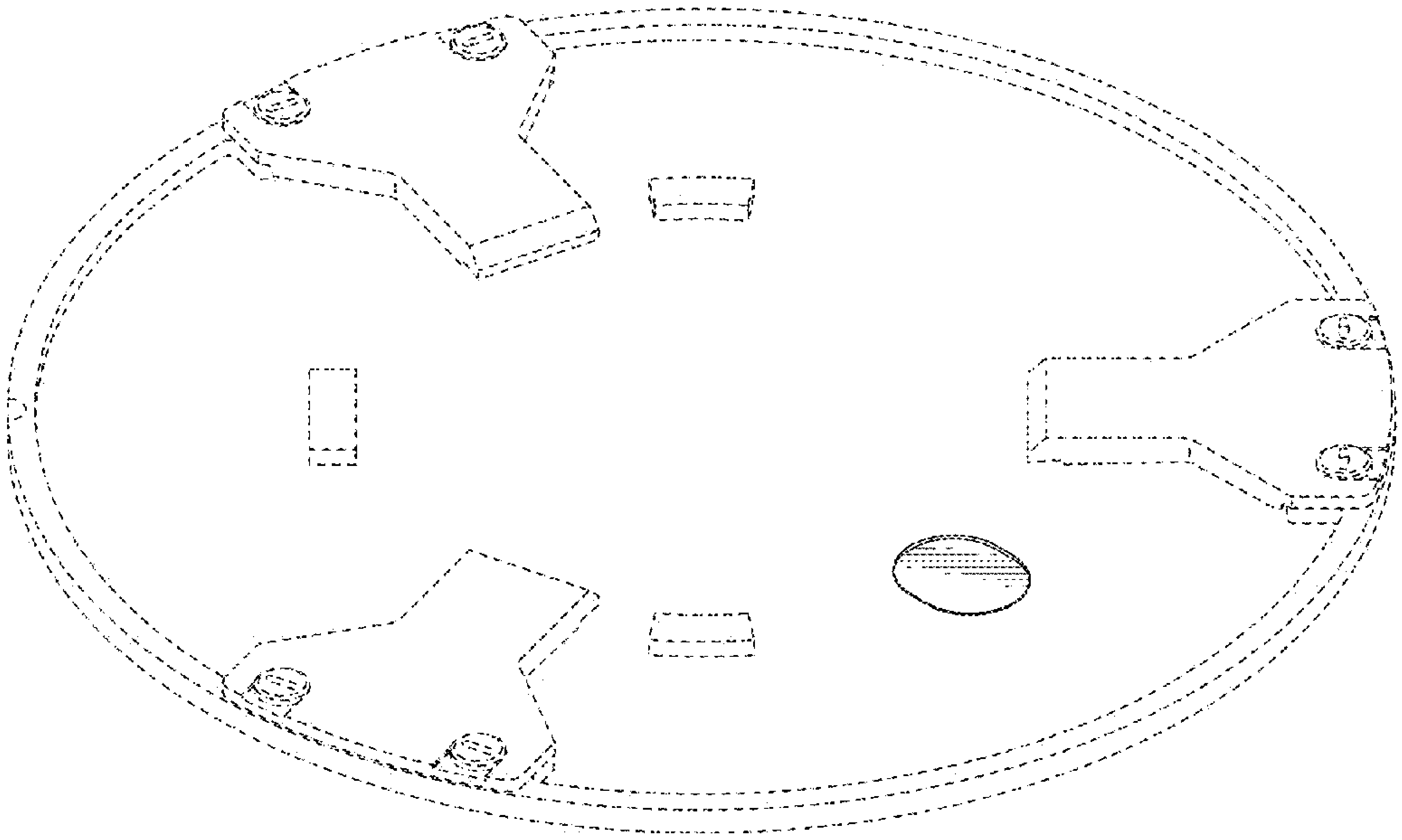


FIG.8